

Highlights

- Formulated to meet the demands of SiC polishing applications
- Achieves higher removal rates and lower pad wear
- Available in multiple surface textures: plain and XY-grooved

Next-generation pad for multi-wafer batch polish

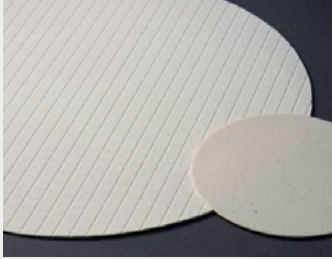
EXTERION™ N4000H

The EXTERION™ pad line uses a new advanced urethane formula specifically to achieve higher removal rates and lower pad wear. The controlled porosity and tight distribution of the pore size result in longer pad lifetime. The EXTERION™ N4000H pad is available without sub-pad, and XY-Grooving for optimal slurry distribution for the large diameter platens.

Polishing pad	Base material	Compressibility [%]	Hardness	Hardness test	Density [g / cm ³]
EXTERION™ N4000H	Urethane	2.4	85	JIS A	0.86
MHS15S	Urethane	3.0	84	JIS A	0.80

Pad product roadmap for SiC wafer polishing

Pad type	Stock Removal Polish with Diamond slurry				CMP-step with KMnO ₄	
	Felt-based pads		Polyurethane-type pads			
	SUBA™ 600	SUBA™ 800	MH	EXTERION™	IC1000™	IKONIC™
SEM [x 100]						
Thickness [mm]	1.25	1.27	1.0	1.0	1.3	1.3
Density [g / cm ³]	0.37	0.41	0.80	0.86	0.80	0.93
Hardness (Shore D)	80 (Asker -C)	84 (Asker -C)	30D	85 (JIS A)	60D	66D



EXTERION™ pads provide significant advantages in achieving consistent, reproducible polishing results.



Pureon offers a variety of slurries in a wide range of viscosities and custom formulations to match EXTERION™ polishing pads. We are happy to assist you in finding the best suitable products.



Pureon offers a wide range of customized solutions. More information can be found on www.pureon.com/products/overview

Product specifications

Base material Urethane
Shelf life 12 months
Applications Silicon carbide, various hard substrates

Application recommendations

Handling Apply only to a clean, dry surface at room temperature. If an appropriate solvent, such as isopropyl alcohol, is used to clean the platen after a pad removal, allow the platen to dry completely and return to room temperature before applying a new pad. Solvents remaining on the platen or an unusually cold platen will lower PSA adhesion.

When applying the pad to the platen, peel the release liner from one edge of the pad. Fold liner back approximately two inches. Align the pad with the edge of the platen and adhere. In one continuous movement, slowly peel the remaining release liner off the pad while pressing the pad down on the platen. The application should be smooth and uniform with even pressure from the pad mounting tool (such as a flat disk or hand roller).

Do not try to reposition pads with PSA adhesive.

Storage Product should be stored and transported in the original packaging. The product should be stored in temperatures between 10 °C to 24 °C (50 °F to 75 °F) and < 50 % humidity. Exposure for six (6) months or less to conditions between -17 °C to 48 °C (0 °F and 120 °F) and / or at relative humidity of up to 100 % will not impact the product performance as long as the release liner remains intact and attached to the PSA. If the product is exposed to temperatures and humidity outside the recommended conditions, it may still be acceptable for use. In all cases, the product should be allowed to return to normal room temperatures prior to use.

Disposal Dispose of in accordance with all applicable local regulations.

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